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12/31/01

U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10038800	12/31/2001	430	313	1756	Datta Barreca

****APPLICANTS:** Ma Ching-Tien; Chen Tsung-Chuan; Hsu Shew-Tsu;

****CONTINUING DATA VERIFIED:** none

**** FOREIGN APPLICATIONS VERIFIED:** none

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed	<input type="checkbox"/> yes <input checked="" type="checkbox"/> no	ATTORNEY DOCKET NO 67,200-549
35 USC 119 conditions met	<input type="checkbox"/> yes <input checked="" type="checkbox"/> no	
Verified and Acknowledged Examiners's initials <i>mg</i>		
TITLE : Method for forming via and contact holes with deep UV photoresist		

U.S. DEPT. OF COMM./PAT & TM-PTO-435L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Sheets Drwg.	Figs. Drwg. Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		Application Examiner	
		PREPARED FOR ISSUE	
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